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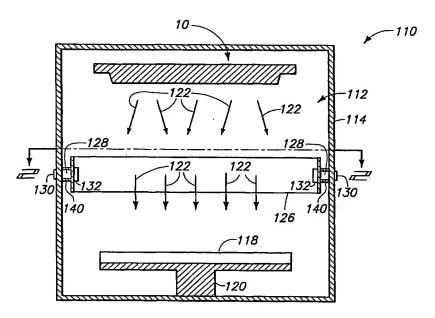
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- (71) Applicant: HONEYWELL INTERNATIONAL INC. [US/US]; 101 Columbia Road, P.O. Box 2245, Morristown, NJ 07960 (US).
- (72) Inventors; and
- (75) Inventors/Applicants (for US only): JAEYEON, Kim [KR/US]; 1018 N. Simpson Road, Liberty Lake, WA 99091 (US). SAYLES, Scott, R. [US/US]; N. 14719 Lowe, Mead, WA 99021 (US). KARDOKUS, Janine,

- K. [US/US]; 23011 East Mocha Lane, Liberty Lake, WA 99019 (US). PHELAN, Terry, J. [US/US]; 4806 North Best Road, Spokane, WA 99216 (US).
- (74) Agents: HOIRIIS, David et al.; Honeywell International Inc., 101 Columbia Road, P.O. Box 2245, Morristown, NJ 07960 (US).
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(54) Title: METHODS OF TREATING DEPOSITION PROCESS COMPONENTS TO FORM PARTICLE TRAPS, AND DEPO-SITION PROCESS COMPONENTS HAVING PARTICLE TRAPS THEREON



(57) Abstract: The invention includes methods for forming particle traps along surfaces of PVD components, and comprises PVD components having particle traps thereon. The invention can include utilization of highly soluble media for bead-blasting and/or can include utilization of metallic materials as bead-blasting media. The invention can also include formation of an insert along regions of a backing plate where particle traps are desired, with the insert being of a composition which has better particle-trapping properties than the backing plate.



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